

FORM PTO-1449				U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. D-95013A		SERIAL NO. <del>Filed Herewith</del> <b>09/141,443</b>	
LIST OF PRIOR ART CITED BY APPLICANT						APPLICANT  Ahmad Waleh et al			
						FILING DATE <del>Filed Herewith</del> <b>8/27/98</b>		GROUP <b>1746</b>	
U.S. PATENT DOCUMENTS									
EXR IN		DOC. NO.	DATE	NAME	CLASS	SUBCLASS			
<b>4M</b>	AA	4,669,544	6/1/87	Nimerick	166	300			
	AB	5,030,399	7/9/91	Walles et al	264	83			
	AC	5,158,100	10/27/92	Tanaka et al	134	105			
	AD	4,179,071	12/18/79	Kozacka	239	397.5			
	AE	4,915,912	4/10/90	Walles et al	422	160			
	AF	4,778,536	10/18/88	Grebinski	134	36			
<b>AM</b>	AG	5,037,506	8/6/91	Gupta et al	156	646			
	AH								
	AI								
	AJ								
	AK								
FOREIGN PATENT DOCUMENTS									
		DOC. NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION		
							YES	NO	
	AL								
	AM								
	AN								
	AO								
	AP								
OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)									
<b>AM</b>	AR	Stanley Wolf and Richard N. Tauber, "Silicon Processing For The VLSI Era", <i>Process Technology</i> , Vol. 1 (1986), p. 564;							
	AS	"Choose The Right Process To Strip Your Photoresist", <i>Semiconductor International</i> , February 1990, pp 83-87;							
	AT	"New Concerns In Dry Oxygen Ashing", <i>Semiconductor International</i> , March 1996, p. 44; and							
<b>AM</b>	AU	"What's Driving Resists Dry Stripping?", <i>Semiconductor International</i> , November 1994, pp 61-64.							
	AV								
	AW								
EXAMINER <b>H. MARKOFF</b>				DATE CONSIDERED <b>11/17/99</b>					
EXAMINER: Initial if references considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.									